



**UNITED NATIONS INDUSTRIAL DEVELOPMENT ORGANIZATION**  
**INVESTMENT AND TECHNOLOGY PROMOTION OFFICE, TOKYO (UNIDO ITPO Tokyo)**  
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***Invitation***

**UNIDO Industrial Development Report 2009 Symposium**

The United Nations Industrial Development Organization (UNIDO), with the support of METI, MOFA, UNU, JICA & IDE-JETRO, is pleased to invite you to a symposium introducing UNIDO's "Industrial Development Report 2009." Dr. John Page, a well known African specialist and one of the co-authors of the report, will reflect on the report's conceptual breakthrough in analyzing the long-term structural change in industry and its implications for the policy. Dr. Vinanchiarachi, who led the UNIDO team in preparing and finalizing the report, will explain the principal findings of the report and show the relevance of UNIDO interventions in terms of technical assistance. This symposium will be also an opportunity for the audience to learn how UNIDO can cooperate with Japan to create and execute most effective projects/programmes for developing countries in the midst of a major global economic downturn.

The symposium will take place on Tuesday, 14 April 2009, from 2:30 pm to 5:20 pm at the Elizabeth Rose Hall of the United Nations University. It will be conducted with English/Japanese simultaneous interpretation.

Advanced registration is required. Please register yourself on the below website.

**<http://www.unido.or.jp/mailform/appform.html>**

Date: 14 April 2009 (Tuesday)  
Time: 14:30 – 17:20 (Registration starts at 14:00) 17:30 - Reception  
Place: Elizabeth Rose Hall (5F), United Nations University (UNU)  
5-53-70 Jingu-mae, Shibuya-ku  
Subway Station "Omotesando" Exit B2  
Access to UNU: <http://www.unu.edu/access/>  
Organizer: UNIDO  
Co-organizers: UNU, JICA(tbc), JETRO-IDE(tbc), UNIDO ITPO Tokyo  
Supporters: METI(tbc), MOFA(tbc)  
Language: English/Japanese simultaneous interpretation  
Admission: Free